

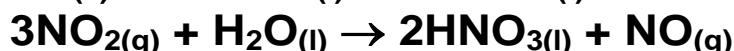
Heterogeneous non catalytic reactions

- solid – fluid (liquid, gas)

- Dissolution of solids (e.g. $\text{MgCO}_{3(\text{s})} + \text{HNO}_{3(\text{l})}$)
- Chemical Vapor Deposition ($\text{SiH}_{4(\text{g})} \rightarrow \text{Si}_{(\text{s})} + 2\text{H}_2$)
- Sublimation ($\text{U}_{(\text{s})} + 3 \text{F}_{2(\text{g})} \rightarrow \text{UF}_{6(\text{g})}$)
- Reduction of solid oxides ($\text{NiO}_{(\text{s})} + \text{H}_{2(\text{g})} \rightarrow \text{Ni}_{(\text{s})} + \text{H}_2\text{O}_{(\text{g})}$)
- Metals oxidation ($\text{Zn}_{(\text{s})} + \text{O}_{2(\text{g})} \rightarrow \text{ZnO}_{(\text{s})}$)
- Catalytic reactions

- liquid – gas

- Dissolution with chemical reaction

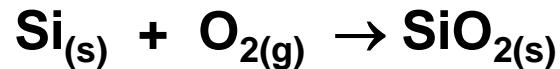


- solid – solid

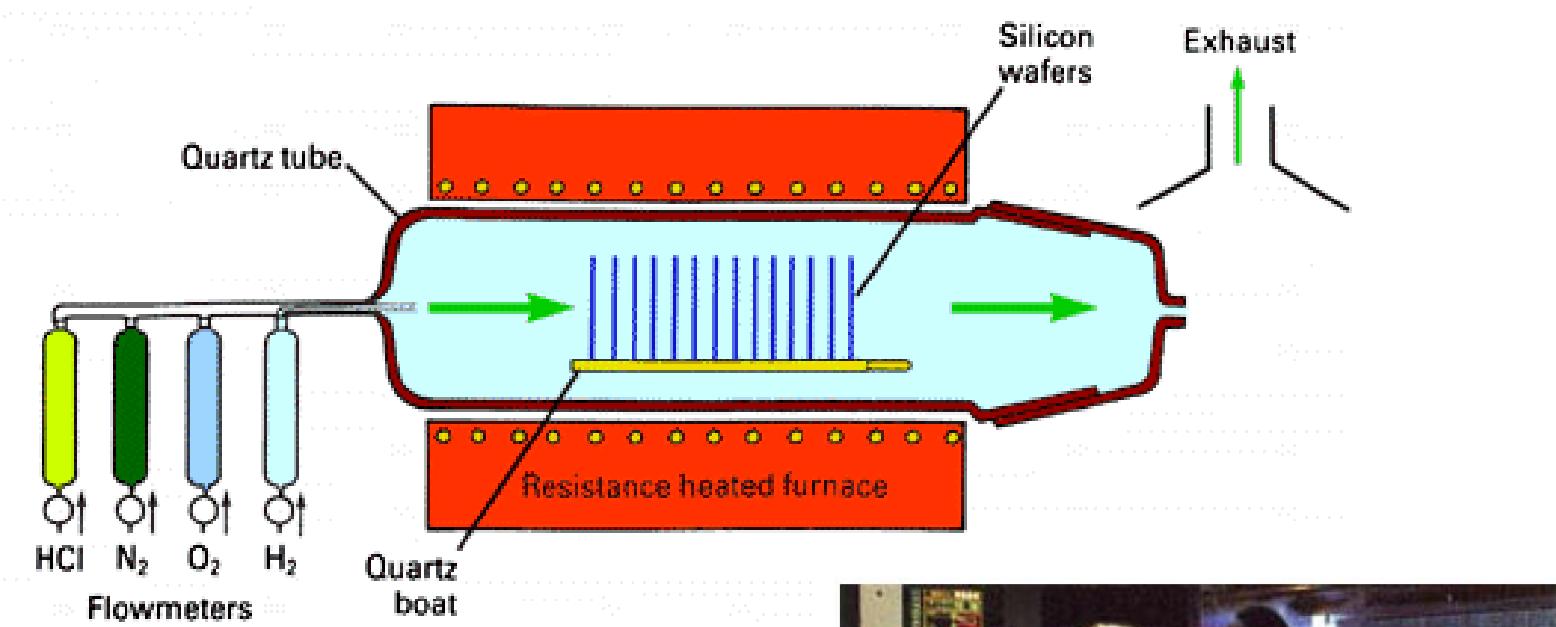
- $\text{CoO}_{(\text{s})} + \text{Al}_2\text{O}_{3(\text{s})} \rightarrow \text{CoAl}_2\text{O}_4_{(\text{s})}$

Heat and mass transfer phenomena affect global reaction rate.

Heterogeneous gas-solid reactions

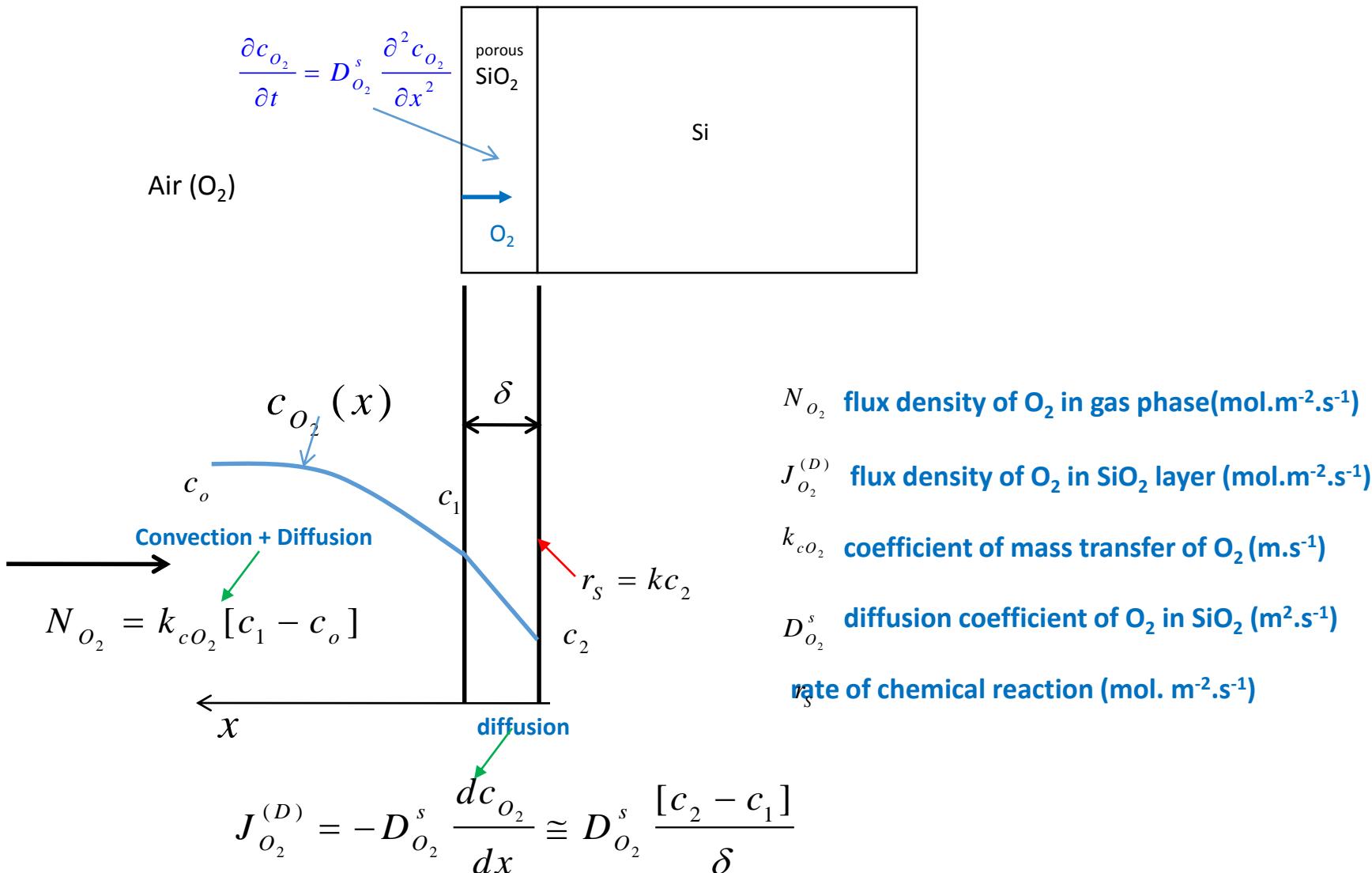
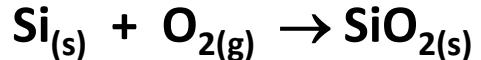


Silicon thermal oxidation is by far most important for silicon devices. It is the key process in modern silicon integrated circuit technology.



Oxidation Furnace
(Silicon Valley Group - Thermco Systems)

Kinetics of gas-solid heterogeneous reaction



Steady state

$$N_{O_2} = J_{O_2}^{(D)} = \nu_{O_2} r_s$$

$$k_{cO_2} [c_1 - c_o] = D_{O_2}^s \frac{[c_2 - c_1]}{\delta} = -k c_2$$

c₁ a c₂ calculation :

$$\left(k_{cO_2} + \frac{D_{O_2}^s}{\delta} \right) c_1 - \frac{D_{O_2}^s}{\delta} c_2 = k_{cO_2} c_o$$

$$-\frac{D_{O_2}^s}{\delta} c_1 + \left(k + \frac{D_{O_2}^s}{\delta} \right) c_2 = 0$$

$$c_1 = \frac{k_{cO_2} \left(k + \frac{D_{O_2}^s}{\delta} \right)}{k \cdot k_{cO_2} + \frac{D_{O_2}^s}{\delta} (k_{cO_2} + k)} c_o$$

$$c_2 = \frac{k_{cO_2} \frac{D_{O_2}^s}{\delta}}{k \cdot k_{cO_2} + \frac{D_{O_2}^s}{\delta} (k_{cO_2} + k)} c_o$$

SiO₂ layer thickness and Si conversion :

reaction rate

$$r_s = \frac{c_o}{\frac{1}{k_{cO_2}} + \frac{\delta(t)}{D_{O_2}^s} + \frac{1}{k}}$$

$$r_s = \frac{\rho_{SiO_2}}{M_{SiO_2}} \frac{d\delta}{dt}$$

$$\left[\frac{1}{k_{cO_2}} + \frac{1}{k} \right] \delta + \frac{1}{2} \frac{\delta^2}{D_{O_2}^s} = c_o \frac{M_{SiO_2}}{\rho_{SiO_2}} t$$

$$\delta = \varpi_o X_{Si}$$

$$\varpi_o = \frac{\delta_o}{2} \frac{M_{SiO_2}}{M_{Si}} \frac{\rho_{Si}}{\rho_{SiO_2}}$$

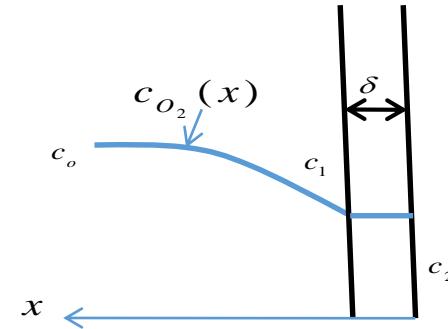
$M_{SiO_2}, M_{Si}, \rho_{SiO_2}, \rho_{Si}$ Molar weights and densities of SiO₂ a Si

δ_o Initial thickness of Si slab

3 limiting cases

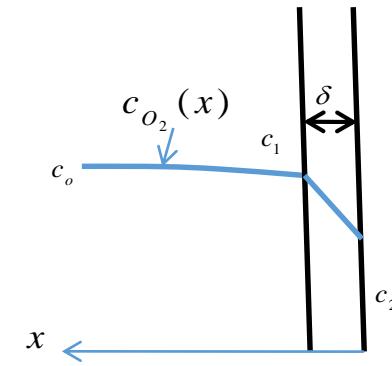
1. Rate determining step is the external mass transfer of oxygen towards interface (gas - SiO_2)

$$\frac{1}{k_{\text{CO}_2}} \gg \frac{\delta}{D_{\text{O}_2}^s}, \frac{1}{k_{\text{CO}_2}} \gg \frac{1}{k} \Rightarrow r_s = k_{\text{CO}_2} c_o, \quad \delta = k_{\text{CO}_2} c_o \frac{M_{\text{SiO}_2}}{\rho_{\text{SiO}_2}} t$$



2. Rate determining step is the internal mass transfer of oxygen in porous SiO_2 layer

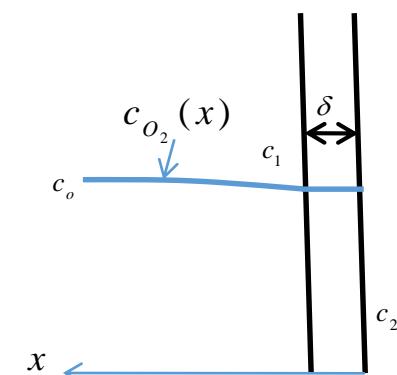
$$\frac{\delta}{D_{\text{O}_2}^s} \gg \frac{1}{k_{\text{CO}_2}}, \frac{\delta}{D_{\text{O}_2}^s} \gg \frac{1}{k} \Rightarrow r_s = \frac{D_{\text{O}_2}^s}{\delta} c_o, \quad \delta = \sqrt{2 D_{\text{O}_2}^s c_o \frac{M_{\text{SiO}_2}}{\rho_{\text{SiO}_2}} t}$$



3. Rate determining step is chemical reaction taking place on the interface (SiO_2 - Si)

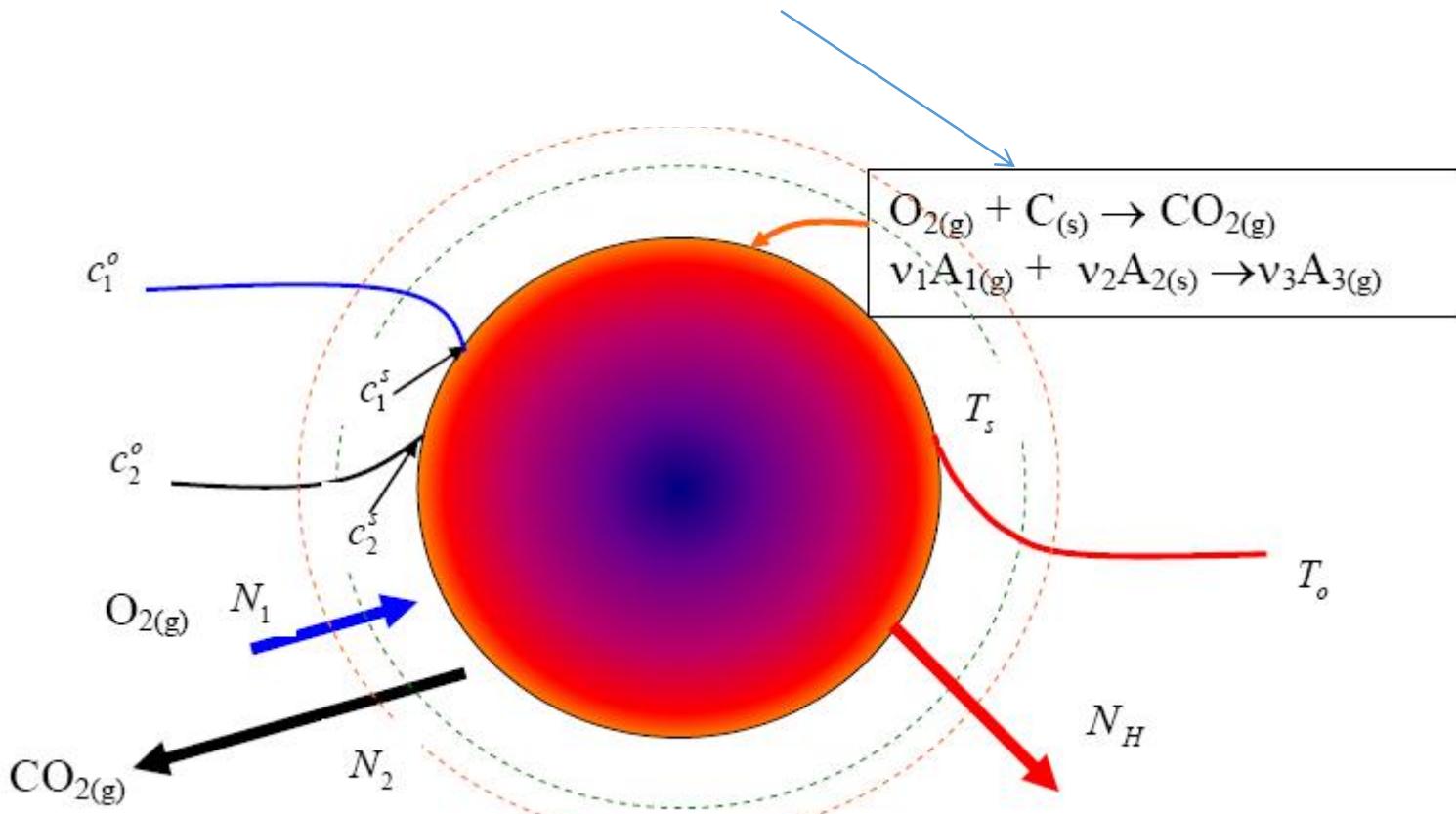
$$\frac{1}{k} \gg \frac{\delta}{D_{\text{O}_2}^s}, \frac{1}{k} \gg \frac{1}{k_{\text{CO}_2}} \Rightarrow r_s = k c_o, \quad \delta = k c_o \frac{M_{\text{SiO}_2}}{\rho_{\text{SiO}_2}} t$$

Discussion: $r_s = f(\text{composition}), r_s = f(\text{temperature})$



External heat and mass transfer

Combustion of the spherical carbon particle



Conditions in the immediate region of an interface between phases are hard to explore experimentally. In such situations it is helpful to develop a mathematical model of the process starting with the known basic facts. The result of the analysis is then compared with those experimental measurements which it is possible to make. Good agreement suggests that the model may have been realistic.

—T. K. Sherwood, R. L. Pigford, and C. R. Wilke (1975)

Oxygen molar flux at steady state

$$N_1 = k_{c1}a(c_1^o - c_1^s) = -v_1r_V = -(-1)k(T_s)c_1^s = \\ = A \exp\left(-\frac{E}{RT_s}\right)c_1^s$$

Energy flux at steady state

$$N_H = ha(T_s - T_o) = (-\Delta H_r)r_V$$

Surface temperature and concentration of oxygen

Two balance equations for unknown c_1^s, T_s

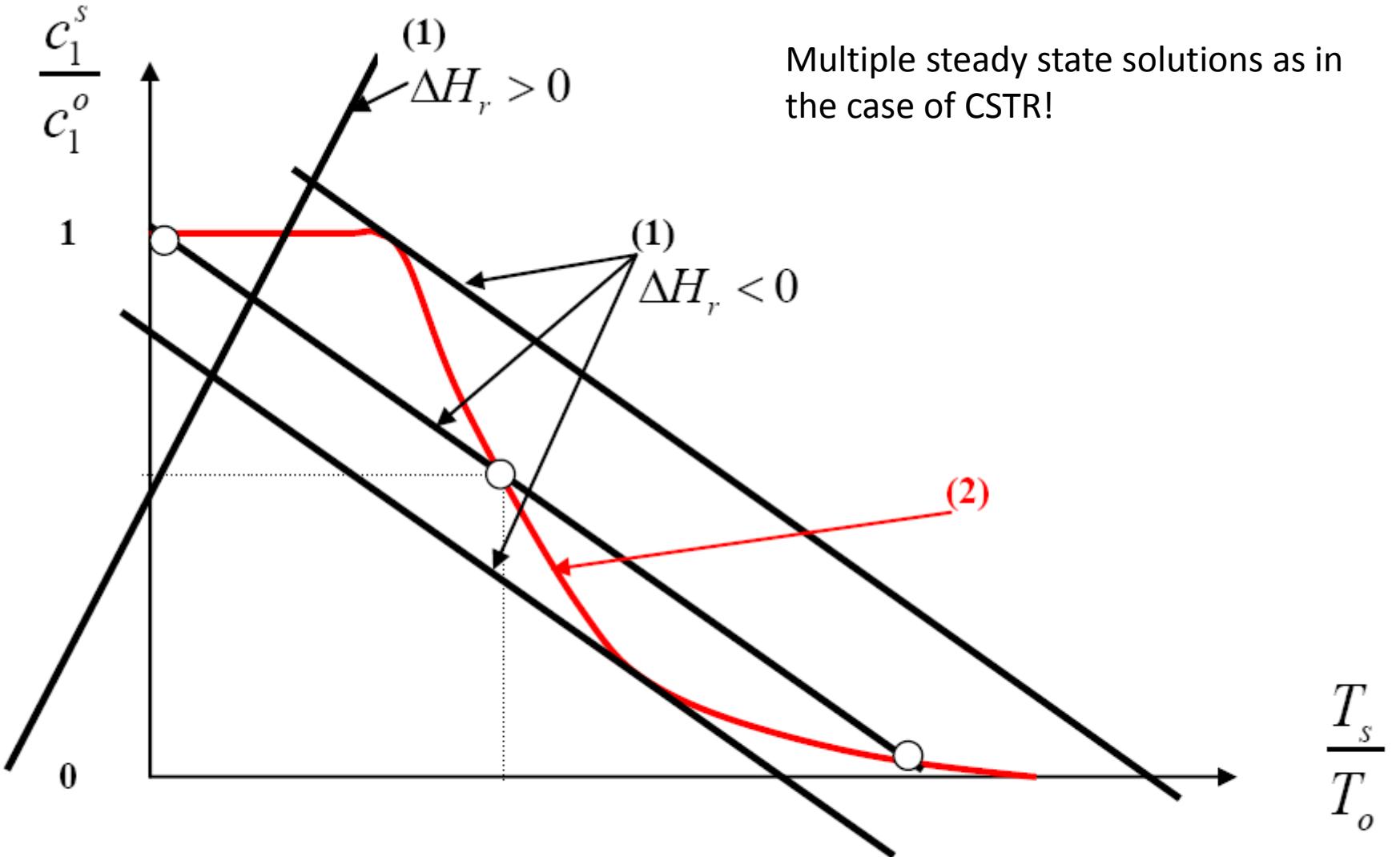
$$ha(T_s - T_o) = (-\Delta H_r)r_V = (-\Delta H_r)k_{c1}a(c_1^o - c_1^s)$$

$$\frac{c_1^s}{c_1^o} = 1 - \frac{hT_o}{(-\Delta H_r)k_{c1}c_1^o} \left(\frac{T_s}{T_o} - 1 \right) \quad (1)$$

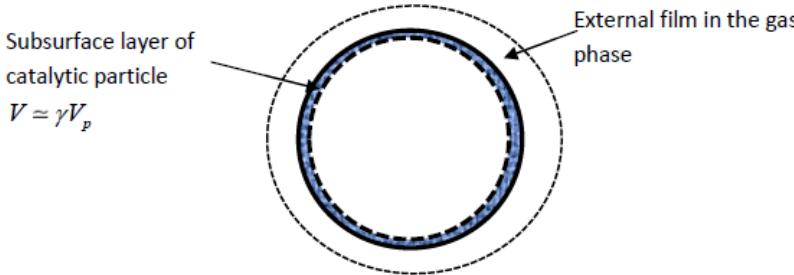
$$k_{c1}a(c_1^o - c_1^s) = k(T_s)(c_1^s)^n$$

$$n = 1$$

$$\frac{c_1^s}{c_1^o} = \frac{k_{c1}a}{k_{c1}a + k(T_s/T_o)} \quad (2)$$



Example



Molar material balances

$$\varepsilon_p \gamma V_p \frac{dc_i}{dt} = S_e k_{e,i} (c_i^G - c_i^S) + \rho_s (1 - \varepsilon_p) \gamma V_p \sum_{j=1}^{NR} \nu_{ji} r_{M,j}$$

Enthalpy balance

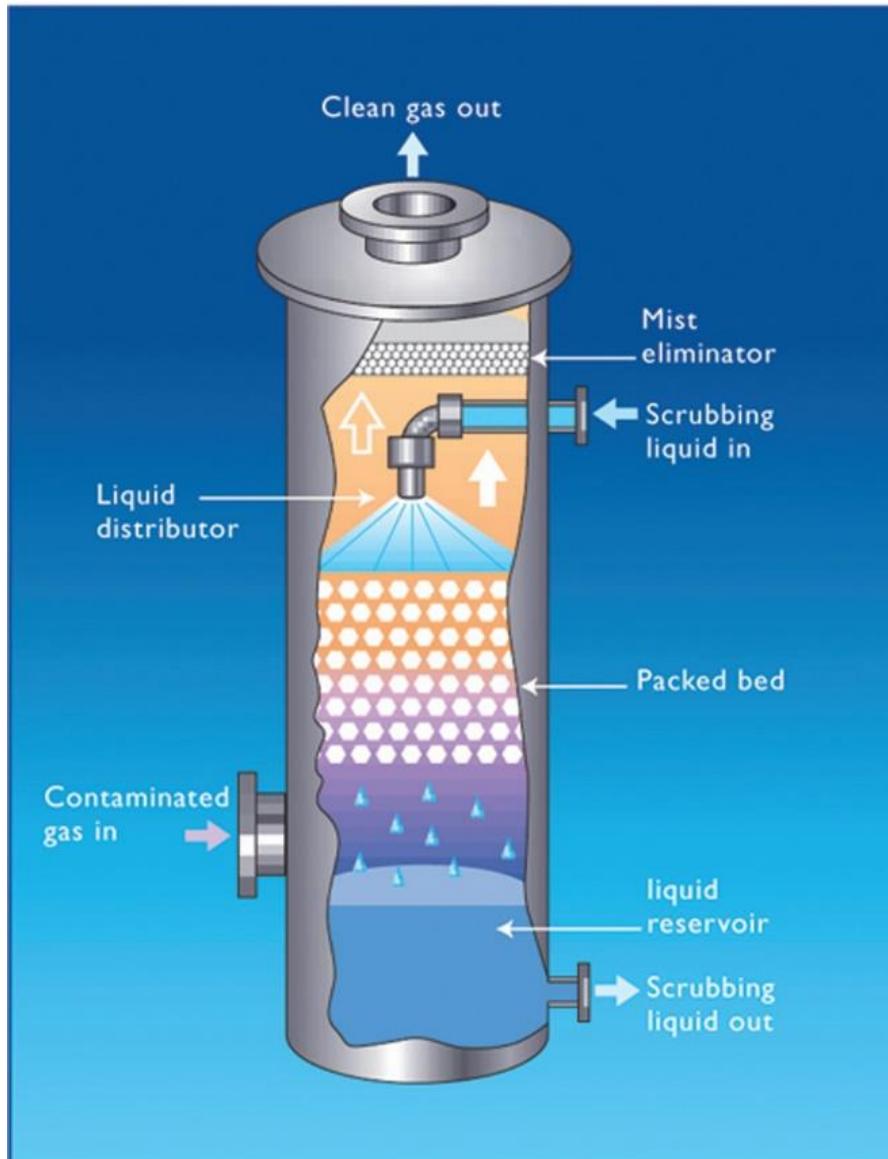
$$\left[(1 - \varepsilon_p) \rho_s V_p c_{pS} + \varepsilon_p V_p \frac{P}{RT_S} c_{pG} \right] \frac{dT_S}{dt} = S_e h (T_G - T_S) + (1 - \varepsilon_p) \gamma \rho_s V_p \sum_{j=1}^{NR} (-\Delta_r H) r_{M,j}$$

$$(1 - \varepsilon_p) \rho_s V_p c_{pS} \frac{dT_S}{dt} = S_e h (T_G - T_S) + (1 - \varepsilon_p) \gamma \rho_s V_p \sum_{j=1}^{NR} (-\Delta_r H) r_{M,j}$$

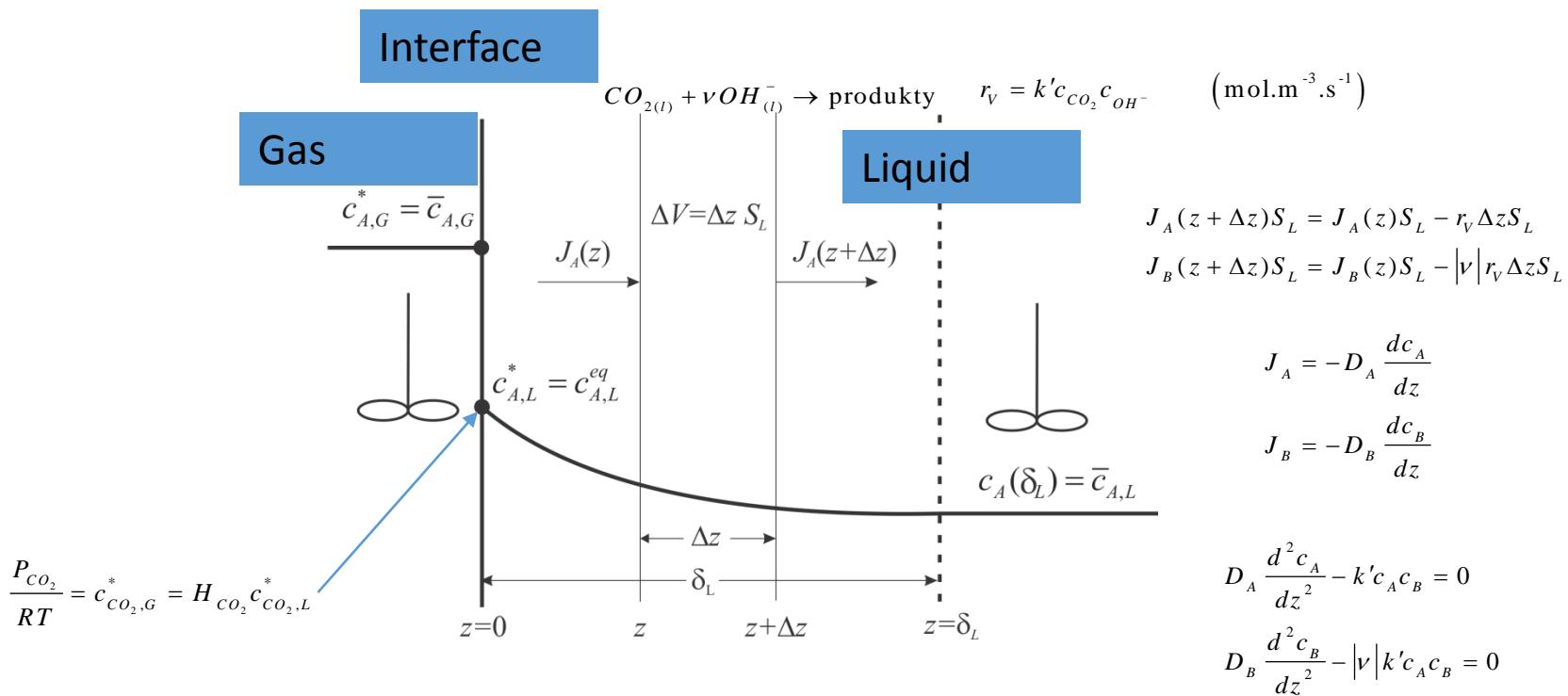
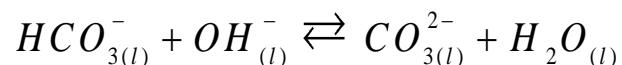
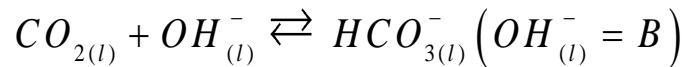
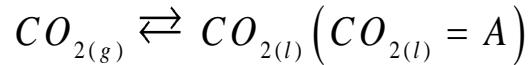


$r_{M,1} = A_1 \exp\left(-\frac{E_1}{RT}\right) P_{s,NH_3} P_{s,O_2} \text{ mol.kg}^{-1}.s^{-1}$	$A_1 = 4.609 \times 10^{+3} \text{ mol.kg}^{-1}.s^{-1}.Pa^{-2}$ $E_1 = 149.1 \text{ kJ.mol}^{-1}$	(1)
$r_{M,2} = A_2 \exp\left(-\frac{E_2}{RT}\right) P_{s,NH_3} P_{s,O_2} \text{ mol.kg}^{-1}.s^{-1}$	$A_2 = 5.0 \times 10^{-2} \text{ mol.kg}^{-1}.s^{-1}.Pa^{-2}$ $E_2 = 61.0 \text{ kJ.mol}^{-1}$	(2)
$r_{M,3} = A_3 \exp\left(-\frac{E_3}{RT}\right) P_{s,NH_3} P_{s,O_2} \text{ mol.kg}^{-1}.s^{-1}$	$A_3 = 2.8 \times 10^{-2} \text{ mol.kg}^{-1}.s^{-1}.Pa^{-2}$ $E_3 = 104.0 \text{ kJ.mol}^{-1}$	(3)

Heterogeneous gas-liquid reactions



Kinetics of gas-liquid reactions



$$D_A \frac{d^2 c_A}{dz^2} - k' c_A c_B = 0$$

$$D_B \frac{d^2 c_B}{dz^2} - |\nu| k' c_A c_B = 0$$

Boundary conditions

$$z = 0 : c_A = c_{A,L}^{eq}, \frac{dc_B}{dz} = 0 \quad \text{Or}$$

$$z = 0; -D_A \frac{dc_A}{dz} = k_{cA,G} (\bar{c}_{A,G} - c_{A,G}^*) = k_{cA,G} (\bar{c}_{A,G} - H_A c_A(z=0)), \frac{dc_B}{dz} = 0$$

$$z = \delta_L : -S_L D_A \frac{dc_A}{dz} = k' c_A \bar{c}_{B,L} (V_L - S_L \delta_L), c_B = \bar{c}_{B,L}$$

Dimensionless form

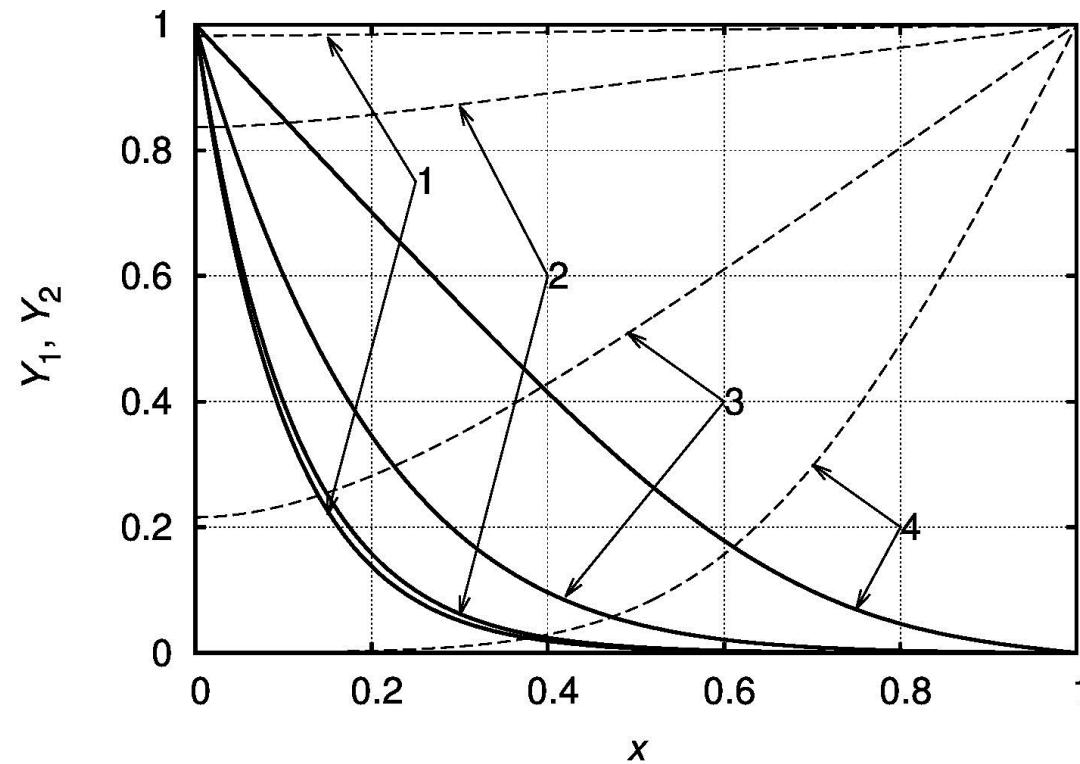
$$x = \frac{z}{\delta_L}, Y_1 = \frac{c_{CO_2}}{c_{CO_2,L}^{eq}} = \frac{c_A}{c_{A,L}^{eq}}, Y_2 = \frac{c_{OH^-}}{\bar{c}_{OH^-,L}} = \frac{c_B}{\bar{c}_{B,L}}$$

$$\begin{aligned} \frac{d^2 Y_1}{dx^2} - Ha^2 Y_1 Y_2 &= 0 & \frac{d^2 Y_2}{dx^2} - \chi Ha^2 Y_1 Y_2 &= 0 \\ x = 0; \quad Y_1 = 1, \frac{dY_2}{dx} &= 0 & x = 1; \quad -\frac{dY_1}{dx} &= Ha^2 Y_1 \left(\frac{V_L}{S_L \delta_L} - 1 \right), Y_2 = 1 \end{aligned}$$

$$Ha = \frac{\sqrt{k' \bar{c}_B D_A}}{D_A / \delta_L} = \frac{\sqrt{k' \bar{c}_B D_A}}{k_{A,L}^o}$$

$$\chi = |\nu| \frac{D_A}{D_B} \frac{c_{A,L}^{eq}}{\bar{c}_{B,L}} \quad k_{A,L}^o = D_A / \delta_L$$

Numerical solution gives to us concentration profiles



We get the overall rate of CO₂ absorption by integration of local rate

$$R_A = -\frac{1}{V_L} \int_0^{V_L} r_V dV$$

$$-\left[-S_L D_A \left(\frac{dc_A}{dz} \right)_{z=0} \right] = V_L R_A$$

$$\frac{S_L D_A c_{A,L}^{eq}}{V_L \delta_L} \left(\frac{dY_1}{dx} \right)_{x=0} = R_A$$

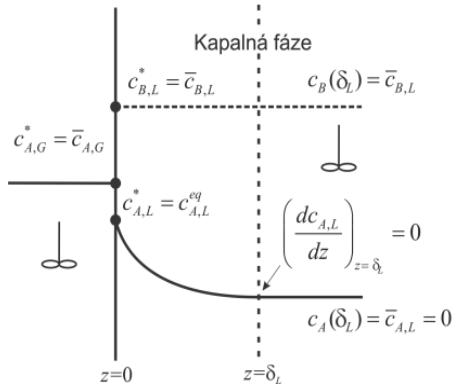
Limiting situations

$$\chi = \left| \nu \right| \frac{D_A}{D_B} \frac{c_{A,L}^{eq}}{\bar{c}_{B,L}} < 10^{-3}$$

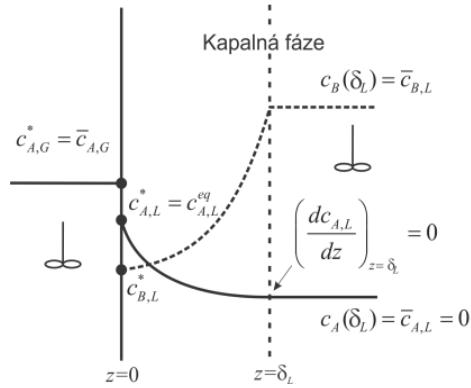
$$\chi = \left| \nu \right| \frac{D_A}{D_B} \frac{c_{A,L}^{eq}}{\bar{c}_{B,L}} > 10^{-2}$$

$$Ha > 3$$

Fázové rozhraní
(g-l)



Fázové rozhraní
(g-l)



Fázové rozhraní
(g-l)

